

SU-8 3050 – run sheet

Kayaku MicroChem / MicroChem Corp.

nanyte.com/photoresists/su-8-3050 · last updated 2026-07-22

Thickness: 44.3–101.3 μm

Softbake: 95 °C · 30 min · hotplate

Post-exposure bake: 95 °C · 4 min

Develop: Developer SU-8 Developer (MicroChem's proprietary solvent-based developer); ethyl lactate and diacetone alcohol are also stated to work · Time 11 min · Rinse Spray/wash with fresh SU-8 developer for ~10 s, then a second spray/wash with isopropyl alcohol (IPA) for ~10 s, then air/nitrogen dry with filtered pressurized gas. A white film appearing during the IPA rinse indicates under-development -- immerse or spray with more SU-8 developer and repeat the rinse. Ultrasonic or megasonic bath agitation is recommended for developing out vias/holes in high-aspect-ratio structures.